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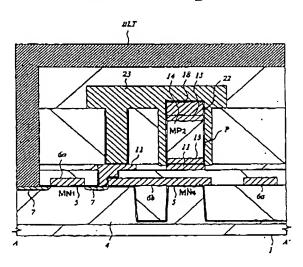
添付公開書頭:

一 国際調査報告書

/統策有]

(54) Title: SEMICONDUCTOR STORAGE AND ITS MANUFACTURING METHOD

(54) 免明の名称: 半導体記憶強度およびその製造方法



(57) Abstract: A memory cell of an SRAM is composed of a transfer MISFET, a drive MISFET, and a load MISFET fabricated over the drive MISFET. The load MISFET has a vertical structure where a gate electrode (23) is disposed over the side face of a multilayer structure (P) extending perpendicularly to a major surface of a semiconductor substrate (1), with a gate insulating film (22) interposed between the gate electrode (23) and the multilayer structure (P). The multilayer structure (P) is composed of polyerystalline silicon films: a lower semiconductor layer (13), an intermediate semiconductor layer (14), and an upper semiconductor layer (15) in order from below.

[梳菜有]

International application No.

	PCT/JE	02/05613		
A. CLASSIFICATION OF SUBJECT MATTER Int.Cl ⁷ H01L27/11, H01L27/108, H01L21/8244, H01L21/8242				
According to International Patent Classification (IPC) or to both a	ational classification and IPC			
B. FIELDS SEARCHED				
Minimum documentation searched (classification system followed by classification symbols) Int.Cl ⁷ H01L27/11, H01L27/108, H01L21/8244, H01L21/8242				
Documentation searched other than minimum documentation to the extent that such documents are included in the fields rearched Jitsuyo Shinan Koho 1922-1996 Toroku Jitsuyo Shinan Koho 1994-2002 Kokai Jitsuyo Shinan Koho 1971-2002 Jitsuyo Shinan Toroku Koho 1996-2002				
Electronic data base consulted during the international search (name of data base and, where practicable, search terms used)				
C. DOCUMENTS CONSIDERED TO BE RELEVANT				
Category* Citation of document, with indication, where a		Relevant to claim No.		
Y 30 March, 1993 (30.03.93), Column 4, line 36 to column 6 JP 5-167040 A	30 March, 1993 (30.03.93), 5,6,9,10 Column 4, line 36 to column 7, line 50			
	05 September, 1997 (05.09.97), Column 5, line 43 to column 8, line 3			
Further documents are listed in the continuation of Box C.	See petent family annex.			
** Special categories of clied documents: "A" document doffning the general state of the an which is not considered to be of particular relevances and comment but published and or after the international filling date. "E" cartier document but published on or after the international filling date. "L" document which may thruw doubts no priority claim(s) or which is clied to caubilish the publication date of another citation or other special mason (as specified). "O' document referring to an oral disclesure, use, exhibition or other means document published prior to the international filing date but later than the priority date calmed. "A" document published after the international filing date but later than the priority date calmed. "A" document published prior to the international filing date but later than the priority date calmed. "A" document member of the same patent family.		he application but cited to derlying the invention cultured invention cannot be ared to involve an inventive of catalogue invention cannot be possible to the document; such a documents, such a skilled in the arifamily		
Date of the actual completion of the informational search 10 September, 2002 (10.09.02) Date of mailing of the international search report 01 October, 2002 (01.10.02)				
Name and mailing address of the ISA/ Japanese Patent Office	Authorized officer			
Facaimile No.	Telephone No.	_		

Form PCT/ISA/210 (second sheet) (July 1998)

International application No.
PCT/JP02/05613

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	mion). DOCUMENTS CONSIDERED TO BE RELEVANT	
Calegory*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
X Y	US 5670803 A (International Business Machines Corp.), 23 September, 1997 (23.09.97), Full text 5 JP 8-241931 A Full text 6 KR 188623 B	17,18 5,6,9,10
X Y	JP 1-265558 A (Sony Corp.), 23 October, 1989 (23.10.89), Page 2, upper right column, line 12 to page 3, lower right column, line 7 (Family: none)	17,18 5,6,9,10
A	JP 2001-28443 A (Hitachi, Ltd.), 30 January, 2001 (30.01.01), Column 14, line 50 to column 15, line 33 & WO 00/70683 A	7,8
X X	US 5994735 A (Mitsubishi Denki Kabushiki Kaisha) 30 November, 1999 (30.11.99), Column 38, line 6 to column 41, line 55; column 4	1-6 27 24
A	line 36 to column 44, line 28 & US 6127209 A. Column 57, line 12 to column 62, line 18; column 6 line 11 to column 65, line 30	29,30
Y A	US 5627390 A (Mitsubishi Denki Kabushiki Kaisha) 06 May, 1997 (06.05.97), Column 14, line 8 to column 15, line 29; Fig. 16 4 JP 7-321228 A	, 19,20 29,30
Y	<pre>JF 6-104405 A (Toshiba Corp.), 15 April, 1994 (15.04.94), Claims 1, 2 (Family: none)</pre>	25,26
A	Shigeyoshi WATANABE et al., A Novel Circuit Technology with Surrounding Gate Transistors(SGT's for Ultra High Density DREAM's. IEEE Journal of Solice State Circuits, Vol.30, No.9, 1995.09, pages 960 6971, full text	4~ {
Form PCT/I	SA/210 (continuation of second sheet) (July 1998)	

International application No.
PCT/JP02/05613

2 2 2		
Box I Observ	ations where certain claims were found unsearchable (Continuation of item 1 of first sheet)	
1 ms internation	al search report has not been established in respect of certain claims under Article 17(2)(a) for the following reasons:	
1. Claims	s Nos.:	
becaus	they relate to subject matter not required to be searched by this Authority, namely:	
ŀ	•	
1		
}	<u>.</u> .	
2. Claima	Nos.:	
because	e they relate to parts of the International application that do not comply with the prescribed requirements to such an	
extent (that no meaningful international search can be carried out, specifically:	
_		
3. Claims		
bezause	they are dependent claims and are not drafted in accordance with the second and third sentences of Rulo 6.4(a).	
Box II Observ	ations where unity of lavention is lacking (Continuation of item 2 of first sheet)	
This International	Searching Authority found multiple inventions in this international application, as follows:	
The inv	Entions of claim 1-18, 21-30 relate to an gram	
23.0 11.0	entions of 19, 20 relate to an SRAM.	
	•	
	•	
1. [Asalin	equired additional search fees were timely paid by the applicant, this international search report covers all searchable	
claims.	- Annual search term was a timery bare by the applicant, this international search report covers all searchable	
2. X As all 50	earchable claims could be scarched without effort justifying an additional fee, this Authority did not invite payment	
of any a	additional fee.	
3. Asonly	SOME OF the remited additional access for a second state of the state of the second st	
only the	some of the required additional search fees were timely paid by the applicant, this international search report covers use claims for which fees were paid, specifically claims Nos.:	
4. No requi	lred additional search fees were timely paid by the applicant. Consequently, this international search report is	
restricted to the invention first mentioned in the claims; it is covered by claims Nos.:		
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Remark on Prote	The additional search fees were accompanied by the applicant's protest.	
	No protest accompanied the payment of additional search fees.	

Form PCT/ISA/210 (continuation of first sheet (1)) (July 1998)

International application No. PCT/JP02/10510

	PCT/JP02/10510
in I Observations where certain claims were found unsearchable (Continuation his international search report has not been each below.	
his international search report has not been established in respect of certain claims under	of item 2 of first sheet)
. Claims Nos.:	er Article 17(2)(a) for the following reasons:
because they relate to subject matter not required to be searched by this Authori	
Authorities and required to be searched by this Authorities	ity, namely:
2. Claims Nos.:	
L	
because they relate to parts of the international application that do not comply we extent that no meaningful international search can be carried out, specifically:	ith the prescribed requirements to
and be carried out, specifically:	reductionents to such an
3. Claims Nos.;	
	j
because they are dependent claims and are not drafted in accordance with the secondance.	and third sentences of Pulo 5 46-2
box if Observations where unity of invention is lacking (Continued)	
As is described on the extra sheet, in order to sa unity of invention, a special technical feature	cation, as follows:
unity of invention, a special technical feature inventions disclosed in the claims as to form a special technical feature	is required to
I CUITCEDE. HOWEVER The	THUTE DEDOLOT INTELL
1 Of inventions: Claims 1 0 4 10	ation includes six groups
of inventions: claims 1, 2, 4-13, claim 3, claims 32, claims 17-21, 33-50, and claims 51-64.	14, 15, claims 16, 22-
(Continued to extra sheet)	1
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1. X As all required additional search fees were timely paid by the applicant, this Interns claims.	1.00
claims.	ational search report covers all searchable
2. As all searchable claims could be	
 As all searchable claims could be searched without effort justifying an additional fee. 	e, this Authority did not invite payment
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3. As only some of the required additional search for any search	
3. As only some of the required additional search fees were timely paid by the applicant only those claims for which fees were paid, specifically claims Nos.:	nt, this international search report covers
was paid, specifically claims Nos.:	
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4. No required additional search fees were timely said but the	i
4. No required additional search fees were timely paid by the applicant. Consequently, restricted to the invention first mentioned in the claims; it is covered by claims Nos.:	this international search report is
the claims; it is covered by claims Nos.:	ĺ
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Remark on Protest X The additional search fees were accompanied by the applicant's	Drotest
No protest accompanied the payment of additional search fees.	protest.
table of auditional search fees.	1
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International application No. PCT/JP02/10510

Continuation of Box No.II of continuation of first sheet(1)

Document 1: JP 63-29571 A (Hitachi Ltd.), 1988.02.08

Document 2: US 5821579 A (LG Semicon C., Ltd.), 1998.10.13

Document 3: US 5670803 A (International Business Machines Corporation), 1997.09.23

The technical feature common to claims 1 to 64 is configuration of "having a gate electrode formed on a side wall of the channel forming region via the gate insulation film".

However, the search has revealed that the configuration of "having a gate electrode formed on a side wall of the channel forming region via the gate insulation film" is not novel since it is disclosed in all the drawings of Document 1, Figures 2 to 4 of Document 2, and all the

As a result the configuration of "having a gate electrode formed on a side wall of the channel forming region via the gate insulation film" makes no contribution over the prior art and cannot be a special technical feature within the meaning of PCT Rule 13.2, second sentence.

Consequently, there is no technical feature common to all the claims.

Since there exists no other common feature which can be considered as a special technical feature within the meaning of PCT Rule 13.2, second sentence, no technical relationship within the meaning of PCT Rule 13 between the different inventions can be seen.

Therefore, it is obvious that claims 1 to 64 do not satisfy the requirement of unity of invention.

- (1) The independent claims 1, 2, 4, 5 have a special technical feature common to them that "a thermal treatment step" is performed after formation of an intermediate semiconductor layer in the longitudinal MISFET manufacturing method.
- (2) The independent claim 3 relates to a longitudinal MISFET manufacturing method but has no special technical feature since the method is disclosed in the aforementioned Documents 1 to 3.
- (3) The independent claim 14 has a special technical feature that in the longitudinal MISFET "the impurities concentration inserted into the intermediate semiconductor layer is low in the region nearer to the lower semiconductor layer and the upper semiconductor layer and high in the region far from the lower semiconductor layer and the upper
- (4) The independent claim 16 relates to a semiconductor storage device manufacturing method but has no special technical feature since the method is disclosed in the aforementioned Documents 1 to 3.
- (5) The independent claims 17, 18, 19, 20, and 21 have a special technical feature common to them that "a thermal treatment step" is performed after formation of the channel formation region in the semiconductor storage device manufacturing method.
- (6) The independent claims 51, 63, 64 relate to a semiconductor storage device but has no special technical feature since the device is disclosed in the aforementioned Documents 1 to 3.

Consequently, the present international application includes six inventions.